

THE PENDING CLAIMS

1. (Previously Presented) A load cup for transferring a substrate in a chemical mechanical polishing system, comprising:
a substrate support adapted to transfer a substrate to a polishing head along a central axis wherein a surface of the substrate support is adapted to retain a liquid bath thereon; and
a first actuator coupled to the substrate support and adapted to move the substrate support laterally to the central axis.
2. (Previously Presented) The load cup of claim 1, wherein the substrate support further comprises:
a peripheral lip extending from the surface of the substrate support and defining a substrate receiving pocket with the surface.
3. (Original) The load cup of claim 2, wherein the lip includes an inner diameter wall having at least a portion thereof disposed at an acute angle relative to the central axis.
4. (Original) The load cup of claim 1 further comprising:
a second actuator coupled to the substrate support and adapted to move the substrate support orthogonally to the first actuator.
5. (Original) The load cup of claim 1 further comprising:
at least a second actuator coupled to the substrate support and adapted to move the substrate support perpendicular to the central axis.
6. (Previously Presented) The load cup of claim 1, wherein the at least one actuator is adapted to move the substrate support in at least two directions perpendicular to an axis defined normal to the surface of the substrate support.

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7. (Original) The load cup of claim 1 further comprising:
a second actuator coupled to the substrate support and adapted to move the substrate support within a plane defined perpendicular to the central axis; and
a third actuator coupled to the substrate support and adapted to move the substrate support in the plane perpendicular to the central axis.
8. (Original) The load cup of claim 1 further comprising:
a sensor adapted to detect the position of the actuator.
9. (Previously Presented) The load cup of claim 1, wherein the liquid bath is adapted to support the substrate.
10. (Original) The load cup of claim 1 further comprising:
a plurality of pins projecting from the surface of the substrate support and adapted to center a substrate relative to a central axis of the substrate support.
- 11-34. (Cancelled)